

ABSTRACT OF THE DISCLOSURE

A pellicle for a photolithographic patterning process by means of a light having a wavelength of from 100 to 200 nm, which has a pellicle membrane made of the 5 following fluoropolymer (A):

Fluoropolymer (A): a substantially linear fluoropolymer which has an alicyclic structure in its main chain, the main chain being a chain of carbon atoms, and which satisfies the following requirements (1) and 10 (2):

(1) the carbon atoms in the main chain comprise a carbon atom having at least one hydrogen atom bonded thereto and a carbon atom having no hydrogen atom bonded thereto; and

15 (2) in the measurement of its high resolution proton magnetic resonance spectrum, the number of hydrogen atoms based on signals appearing on the higher magnetic field side than 2.8 ppm, is at most 6 mol% based on the total hydrogen atoms.